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(21) Application number: **2001115128**(71) Applicant: **CANON INC**(22) Date of filing: **13.04.01**(72) Inventor: **OKADA TAKESHI**

(54) **INLINE TYPE FILM DEPOSITION APPARATUS,
 FILM DEPOSITION METHOD AND LIQUID
 CRYSTAL ELEMENT**

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(57) Abstract

PROBLEM TO BE SOLVED: To provide an inline type film deposition apparatus saving a space decreasing the necessary number of carriers and having excellent maintainability, to provide a transparent conductive film deposition method using the apparatus in which the film with excellent property such as low internal stress, specific resistance and high transparency is produced and is suitable for a color filter, and a liquid crystal element using a high performance color filter produced by the film deposition method.

SOLUTION: In the inline type film deposition apparatus, a return chamber is kept in vacuum, a heating means for carrying out heat treatment accelerating the crystallization of a thin film on a film deposited substrate is provided. The film deposition chamber and the return chamber are adjacently installed to keep a vacuum state.

